

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau



(43) International Publication Date
3 June 2010 (03.06.2010)

PCT

(10) International Publication Number
WO 2010/062508 A1

(51) International Patent Classification:

C11D 3/37 (2006.01) *C11D 7/50* (2006.01)
C11D 7/26 (2006.01) *C11D 11/00* (2006.01)
C11D 7/32 (2006.01) *G03F 7/42* (2006.01)
C11D 7/34 (2006.01) *H01L 21/02* (2006.01)

(21) International Application Number:

PCT/US2009/061585

(22) International Filing Date:

22 October 2009 (22.10.2009)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

61/108,942 28 October 2008 (28.10.2008) US

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(81) Designated States (*unless otherwise indicated, for every*

kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (*unless otherwise indicated, for every*

kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

— *with international search report (Art. 21(3))*

(54) Title: GLUCONIC ACID CONTAINING PHOTORESIST CLEANING COMPOSITION FOR MULTI-METAL DEVICE PROCESSING

(57) Abstract: A microelectronic photoresist cleaning composition suitable for cleaning multi-metal microelectronic devices and to do so without any substantial or significant galvanic corrosion occurring when there is a subsequent rinsing step employing water.



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